Karl Suss MA6 Mask Aligner Standard Operating Procedure

QUICK GUIDE

PROCEDURE OVERVIEW

- 1. Load mask and substrate
- 2. Alignment
- 3. Exposure and unloading

CRITICAL PRECAUTIONS AND COMMON MISTAKES

- Check that lamp is on. If not, contact staff
- Check that stage is homed (x = 10, y = 10, rotation centered)
- In general, mask has to be bigger than the sample

Tool condition for the next user

- Leave MA6 and the TV monitor on.
- Home the stage (X and Y = 10, rotation on center)



Page 2 of 7

FULL PROCEDURE

A) Load mask and substrate:



 Press "Edit parameters" to set up your program Use left/right arrow keys to move between different categories, use up/down keys to change values within category Choose appropriate exposure time, exposure type, alignment gap For basic exposure on Si: Hard contact, with HC wait = 5 sec, Align gap = 50 	
 When done modifying the parameters, press "Edit parameters" again to get back to loading. 	
 To load the wafer: Press "load" and pull the wafer loading chuck out. Press "enter" to turn on the vacuum. If your sample does not cover all vacuum holes, MA6 will report "a loss of vacuum". Press "enter" to acknowledge that and proceed without vacuum. 	Regardless of the size of your sample, always place it into the center of the chuck and make sure that it covers all open vacuum holes.
 Slide the chuck back. Press "enter" again to confirm. 	

B) Alignment (optional, if no alignment, skip to part C: Exposure)

1.	Focus.	Two knobs under "top substrate" on the lower panel are for fine focusing.The big 2" aluminum knob on top of the microscope body is for coarse focusing.
2.	The positions of the objectives can be adjusted with the key	 X(left), X(right), Y(up), Y(down) a. Pressing the "fast" key with the previous keys makes movement faster. b. The distance between objectives can be adjusted by the two 1"-long aluminum knobs on the side of the microscope housing. c. If your sample is small, choose which objective you

		would like to use and move it to the center.		
3.	The gap (Z value) between the substrate	Use the key SEP(up) and SEP(down).		
	and the mask needed for alignment can	. The gap can also be set by "Al. Gap" in "edit		
	be adjusted	parameter".		
		c. To change "Al. Gap", press "edit parameter", and		
		use the X-arrow key to select and the Y-arrow key		
		to change.		
		d. "Fast"+"Y-arrow" enables changing with larger		
		steps.		
		e. Pressing and holding the Y-arrow key makes the		
		parameter go faster, too.		
4.	Align the substrate to the mask using	When properly aligned, press "alignment check" to		
	the three knobs (X, Y, and rotation).	bring the substrate in to contact (contact mode was		
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5.	the three knobs (X, Y, and rotation). Reference points can be stored thus the	bring the substrate in to contact (contact mode was chosen in previous steps.) a. A capturing option is provided to further improve		
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5.	the three knobs (X, Y, and rotation). Reference points can be stored thus the stage will automatically drive between them allowing the alignment to be checked at different locations.	 bring the substrate in to contact (contact mode was chosen in previous steps.) a. A capturing option is provided to further improve alignment accuracy at the high magnification. b. Using this options one can: (i) (i) (i) 		
5.	the three knobs (X, Y, and rotation). Reference points can be stored thus the stage will automatically drive between them allowing the alignment to be checked at different locations.	 bring the substrate in to contact (contact mode was chosen in previous steps.) a. A capturing option is provided to further improve alignment accuracy at the high magnification. b. Using this options one can: (i) (i)		
5.	the three knobs (X, Y, and rotation). Reference points can be stored thus the stage will automatically drive between them allowing the alignment to be checked at different locations.	 bring the substrate in to contact (contact mode was chosen in previous steps.) a. A capturing option is provided to further improve alignment accuracy at the high magnification. b. Using this options one can: (i) Focus on the mask, capture the image of the mask, and then (ii) Switch focus to the substrate surface and 		
5.	the three knobs (X, Y, and rotation). Reference points can be stored thus the stage will automatically drive between them allowing the alignment to be checked at different locations.	 bring the substrate in to contact (contact mode was chosen in previous steps.) a. A capturing option is provided to further improve alignment accuracy at the high magnification. b. Using this options one can: (i) Focus on the mask, capture the image of the mask, and then (ii) Switch focus to the substrate surface and align the substrate fiducials to the virtual 		



C) Exposure and unloading:

1.	Press "exposure" to bring the wafer into	Wait until the exposure is done; follow the	
	contact (if not in contact already) and	instructions on LCD display.	
	expose.		
2.	Pull the wafer loading chuck out completely and unload your sample.	If for any reason you need to unload the wafer before the exposure, press "unload" to pull the chuck out.	
3.	If you need to change the mask, press "change mask" and follow the instruction on the LCD display.		

D) Finishing up:

When done you must	• Home the stage V. V and retation
when done, you must:	• Home the stage A, Y and rotation
	 Leave MA6 and the TV monitor on.



Version history

Draft	Date	Author	Notes on changes
v.0.1	December 7, 2017	Roman	Small changes to initial draft
V2	10/29/2018	Roman	Adding more images